



제25회 한국반도체학술대회

The 25th Korean Conference on Semiconductors

2018년 2월 5일(월)-7일(수), 강원도 하이원리조트 컨벤션 호텔

2018년 2월 6일(화), 09:00-10:45

Room C (함백, 5층)

D. Thin Film Process Technology 분과

[TC1-D] Oxide Thin Film Transistor

TC1-D-1 09:00-09:15	Solution-Processed Rb-Doped Indium Zinc Oxide Thin Film Transistors Sang-Woo Kim, Manh-Cuong Nguyen, An Hoang-Thuy Nguyen, Jung-Yeon Kim, Su-Jin Choi, Hyung-Min Ji, Jong-Gyu Cheon, Kyoung-moon Yu, Jin-Hyun Kim, Seong-Yong Cho, and Rino Choi <i>Department of Materials Science & Engineering, Inha University</i>
TC1-D-2 09:15-09:30	Low-Frequency Noise Characteristics for P-channel SnO Thin Film Transistors with Spray-Coated Carbon Nanotubes Electrodes Jae Hyun Ryu ¹ , Kyung Seop Shin ¹ , Soohun Kowon ² , Hyuck-In Kwon ² , and Sung Hun Jin ¹ <i>¹Department of Electronic Engineering, Incheon National University, ²School of Electrical and Electronics Engineering, Chung-Ang University</i>
TC1-D-3 09:30-09:45	Discharge Current Analysis Estimating the Defect Sites in Amorphous Hf-In-Zn-O Oxide Thin Film Transistor Youngin Goh and Sanghun Jeon <i>Department of Applied Physics, Korea University</i>
TC1-D-4 09:45-10:00	Flexible Charge Trap Memory Thin-Film Transistors Using Conducting Polymer Electrodes and Oxide Semiconductors on Plastic PEN Substrates Ji-Hee Yang ¹ , Da-Jeong Yun ¹ , Seong-Min Kim ² , Myung-Han Yoon ² , and Sung-Min Yoon ¹ <i>¹Department of Advanced Materials Engineering for Information and Electronics, Kyung Hee University, ²School of Materials Science and Engineering, GIST</i>
TC1-D-5 10:00-10:30	[초청] Atomic Layer Deposition of Tin Oxides for Versatile Applications Jeong Hwan Han <i>Department of Materials Science and Engineering, Seoul National University of Science and Technology (Seoultech)</i>
TC1-D-6 10:30-10:45	Effect of Strontium Doping on Indium Zinc Oxide Thin Film Transistors Fabricated by Low-Temperature Solution Process Jin-Hyun Kim, Manh-Cuong Nguyen, An Hoang-Thuy Nguyen, Sang-Woo Kim, Jung-Yeon Kim, Su-Jin Choi, Jong-GyuCheon, Hyung-Min Ji, Kyoung-Moon Yu, Seong-Yong Cho, and Rino Choi <i>Department of Materials Science and Engineering, Inha University</i>